



IFW

PATENT
Attorney Docket No. 1197-245

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)	
)	
Ryuichiro Kanatani et al.)	Group Art Unit: 1752
)	
Application No.: 10/520,417)	Examiner: John S. Y. Chu
)	
Filed: January 6, 2005)	
)	
For: Highly Heat-Resistant,)	Confirmation No.: 5262
Negative-Type Photosensitive)	
Resin Composition)	

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

SUPPLEMENTAL REPLY

In supplement to the Reply filed July 11, 2006, please amend the
above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims in this paper.

Remarks/Arguments follow the amendment section of this paper.